Abstracts

Mapping the thickness of conducting layers by a mm-wave near-field microscope

A.F. Lann, M. Golosovsky, D. Davidov and A. Frenkel. "Mapping the thickness of conducting layers by a mm-wave near-field microscope." 1998 MTT-S International Microwave Symposium Digest 98.3 (1998 Vol. III [MWSYM]): 1337-1340.

We describe a quantitative contactless technique of mapping resistivity of conducting films using a 80 GHz near-field scanning probe. We report (i) a capacitive method of maintaining constant probe-sample separation; (ii) a quantitative measurements of near-field mm-wave reflectivity of conducting films.

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